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(54) **Title:** RADIATION CURABLE COMPOSITION FOR WATER SCAVENGING LAYER, AND METHOD OF MANUFACTURING THE SAME

(57) **Abstract:** A radiation curable resin composition comprising: (A) metal oxide particles; (B) at least one photoinitiator, preferably a radical photoinitiator, or any mixture thereof; (C) at least one acrylate or methacrylate component with a Clog P higher than 2, preferably higher than 4, more preferably higher than 5, or any mixture thereof; (D) at least one monofunctional acrylate or methacrylate diluent component, preferably with a viscosity below 40 mPa·s at 20°C, or any mixture thereof; (E) at least one acrylate or methacrylate component with functionality equal or higher than 3, preferably 3 or 4, or any mixture thereof; can be advantageously used, for example, in multilayer barrier stack for the production of organic opto-electric or opto-electronic device, such as Organic Light Emitting Diode (OLED).

